DuPont™ PlasmaSolv®
EKC270™
Post-Etch Residue Remover

DuPont™ PlasmaSolv® EKC270™ post-etch residue remover is made with DuPont™ HDA® hydroxylamine technology for enhanced performance.

Benefits
• Formulated for optimum metal stack integrity
• “Improved” wide window process capability
• Enhanced post etch residue removal
• Patented and patent pending improved reduction chemistry
• Ultra Large Scale Integration (ULSI) grade specifications for advanced wafer cleaning
• Low evaporation rate at operating temperature

Figure 1. DuPont™ PlasmaSolv® EKC270™ demonstrates superior performance, even under aggressive processing conditions (75 °C for 50 min)

1a. Conventional Remover

1b. DuPont™ EKC270™

Super Clean; Maintaining Metal Integrity
For more information on DuPont™ PlasmaSolv® EKC270™ or other DuPont products, please visit our website.

The information provided in this data sheet corresponds to our knowledge on the subject at the date of its publication. It may be subject to revision as new knowledge and experience becomes available. This information is not intended to substitute for any testing you may need to conduct to determine for yourself the suitability of our products for your particular purposes. Since we cannot anticipate all variations in end-use and disposal conditions, DuPont makes no warranties and assumes no liability in connection with any use of this information. It is intended for use by persons having technical skill, at their own discretion and risk. Nothing in this publication is to be considered as a license to operate under or a recommendation to infringe any patent right.

CAUTION: Do not use in medical applications involving permanent implantation in the human body. For other medical applications, see "DuPont Medical Caution Statement," H-50102-5 and "DuPont Policy Regarding Medical Applications" H-50103-5.

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